

Edwards STP-H451C Technical Specifications

Inlet flange size	ISO160K	
Pumping speed, N ₂ /H ₂	450/300	Litres/second
Compression ratio N_2/H_2	>108/103	
Ultimate pressure	10-7 (10-9)	Pa (Torr)
Maximum continuous outlet pressure*	665 (5)	Pa (Torr)
Maximum Nitrogen throughput*	2500 (4.2)	sccm (Pa m³/sec)
Rated speed	48000	rpm
Starting time	4	minutes
Maximum inlet flange temperature [‡]	120	°C
Power consumption (Max, without TMS)	600	VA
Input voltage	100 - 240	V
Weight, pump/controller	15/9	kg

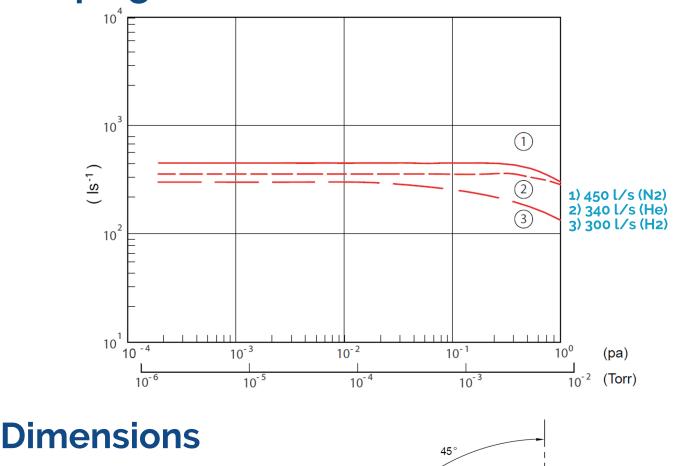
*water cooled [‡] with cooling



PROVAC SALES, INC. 3131 SOQUEL DRIVE, SOQUEL CA 95073



Edwards STP-H451C **Pumping Curves**

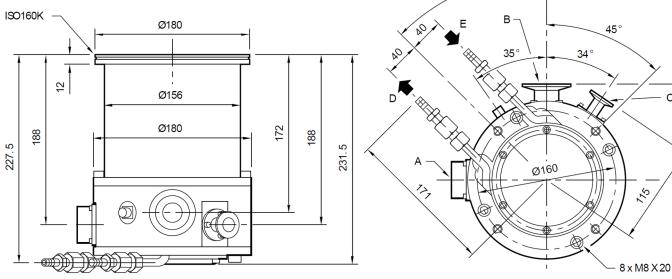


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Edwards STP-H451C Features & Benefits

- designed for use in the harshest of semiconductor applications
- advanced half rack controller design with self-diagnostic functions
- advanced rotor technology
- higher gas throughput
- low noise & vibration
- maintenance free, increased life
- compact design, small footprint
- 5-axis magnetic suspension system
- operation in any orientation
- oil free, zero contamination

Applications

 plasma etch · ECR etch · film deposition · sputtering · ion implantation source · beam line pumping end station · MBE · diffusion · photo resist stripping · crystal, epitaxial growth · wafer inspection · load lock chambers · surface analysis · mass spectrometry · electron microscopy · high energy physics · semiconductor